## Supplementary Materials



Figure S1, <sup>1</sup>H NMR spectrum of TNPP

19 材	材料系-古里密热-大分	7 12 5780								
		J 13.0700	01.11.19 16:16	Su	Index 3	0.000	5.848	N: 11.12 C: 65.03 S: 0.006 H: 4.345	14444 58773 2 10594	0.9779 0.9972 1.0500 0.9796
20 大	大分子有机物(补)	3.1740	01.11.19 16:28		Index 3	0.000	5.900	N: 11.18 C: 65.95 S: 0.000 H: 4.819	12883 52885 0 10397	0.9779 0.997 1.050 0.979
21 大	大分子有机物(补)	3.4250	01.11.19 16:40		Index 3	0.000	5.901	N: 11.02 C: 65.02 S: 0.000 H: 4.745	13702 56256 0 11153	0.977 0.997 1.050 0.97

Figure S2, elemental analysis of TNPP



Figure S3. The Nf-TNPP film OWG sensor response to 100 ppm of inorganic gases at 650 nn



Figure S3. The Nf-TNPP film OWG sensor response to 100 ppm of inorganic gases at 532 nn



Figure S4. The Nf-TNPP film OWG sensor response to 100 ppm of VOCs at 650 nn



Figure S4. The Nf-TNPP film OWG sensor response to 100 ppm of VOCs at 650 nn



Figure S5. The Nf-TNPP film OWG sensor response to 100 ppm of amines at 650 nn



Figure S5. The Nf-TNPP film OWG sensor response to 100 ppm of amines at 532 nn



Figure S6. Absorption spectra of Nf-TNPP film before and after exposure to  $H_2S$  and EDA gas vapours (350-750 nm)



Figure S6. Absorption spectra of Nf-TNPP film before and after exposure to  $H_2S$  and EDA gas vapours (490-750 nm)



**Figure S7.** The Nf-TNPP film OWG sensor response to 100 ppm of H2S in presence of interfereing gases at 650 nn



**Figure S7.** The Nf-TNPP film OWG sensor response to 100 ppm of EDA in presence of interfereing gases at 532 nn